

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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| In re United States Patent Application of: |) | Docket No.: | 020732-97.668 | |
| |) | | (7493) | |
| Applicants: |) | Conf. No.: | 4823 | |
| RATH, Melissa K., et al. |) | | | |
| Application No.: | 10/792,038 |) | Art Unit: | 1752 |
| Date Filed: | March 3, 2004 |) | Examiner: | LE, Hoa Van |
| Title: | COMPOSITION AND PROCESS FOR POST-ETCH REMOVAL OF PHOTORESIST AND/OR SACRIFICIAL ANTI-REFLECTIVE MATERIAL DEPOSITED ON A SUBSTRATE |) | Customer No.: | 24239 |

AMENDMENT RESPONDING TO OCTOBER 19, 2007 OFFICE ACTION AND REQUEST
FOR A ONE-MONTH EXTENSION UNDER 37 CFR §1.136(a) IN UNITED STATES
PATENT APPLICATION NO. 10/792,038

Mail Stop Amendment
Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450

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This responds to the October 19, 2007 Office Action in the above-identified application.

Please amend the claims, as set out in the following Section I (the Claims).

Remarks addressing the substance of the October 19, 2007 Office Action are set out in the **Section II (Remarks)** hereof.